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Client Reference: P-1790.000-US



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: OTTENS et al.

Application No.: 10/743,272

Confirmation No.: 4455

Filed: December 23, 2003

Group No.: 1756

Examiner: TBA

For: OPTIMIZED CORRECTION OF WAFER THERMAL DEFORMATIONS IN A LITHOGRAPHIC PROCESS

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

SUPPLEMENTAL APPLICATION DATA SHEET
37 C.F.R. § 1.76(c)

The following information on the Application Data Sheet is changed as indicated:

BIBLIOGRAPHIC DATA

1. Applicant information is being added.

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